

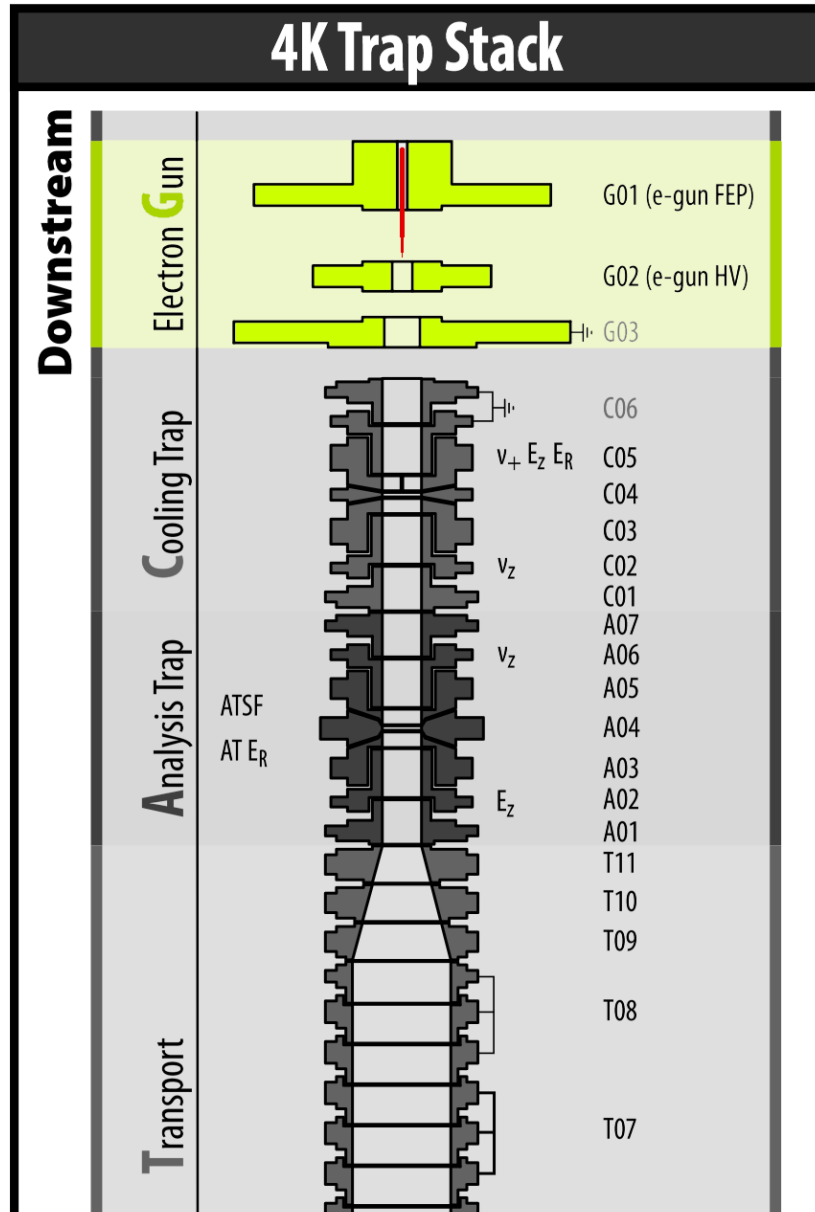
# Production of new E-gun tips

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Philip Geißler, 13.09.2021 – 12.12.2021

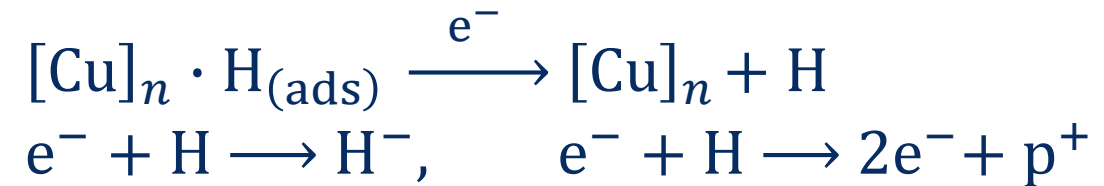


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- BASE E-gun

- $H^- / p^+$  creation via target collision of electrons and copper mesh with adsorbed hydrogen



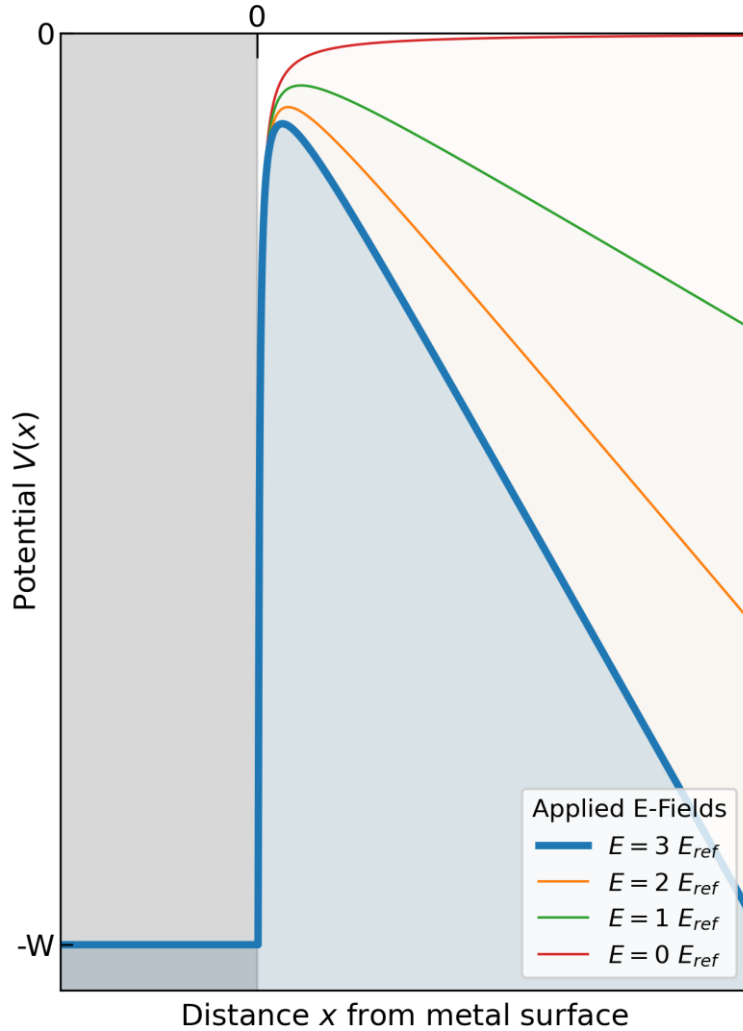
- Electron cooling

$H^- / \bar{p}$  energy transfer to electrons,  
energy emission via synchrotron radiation

- Tips become dull over time  
→ need replacement

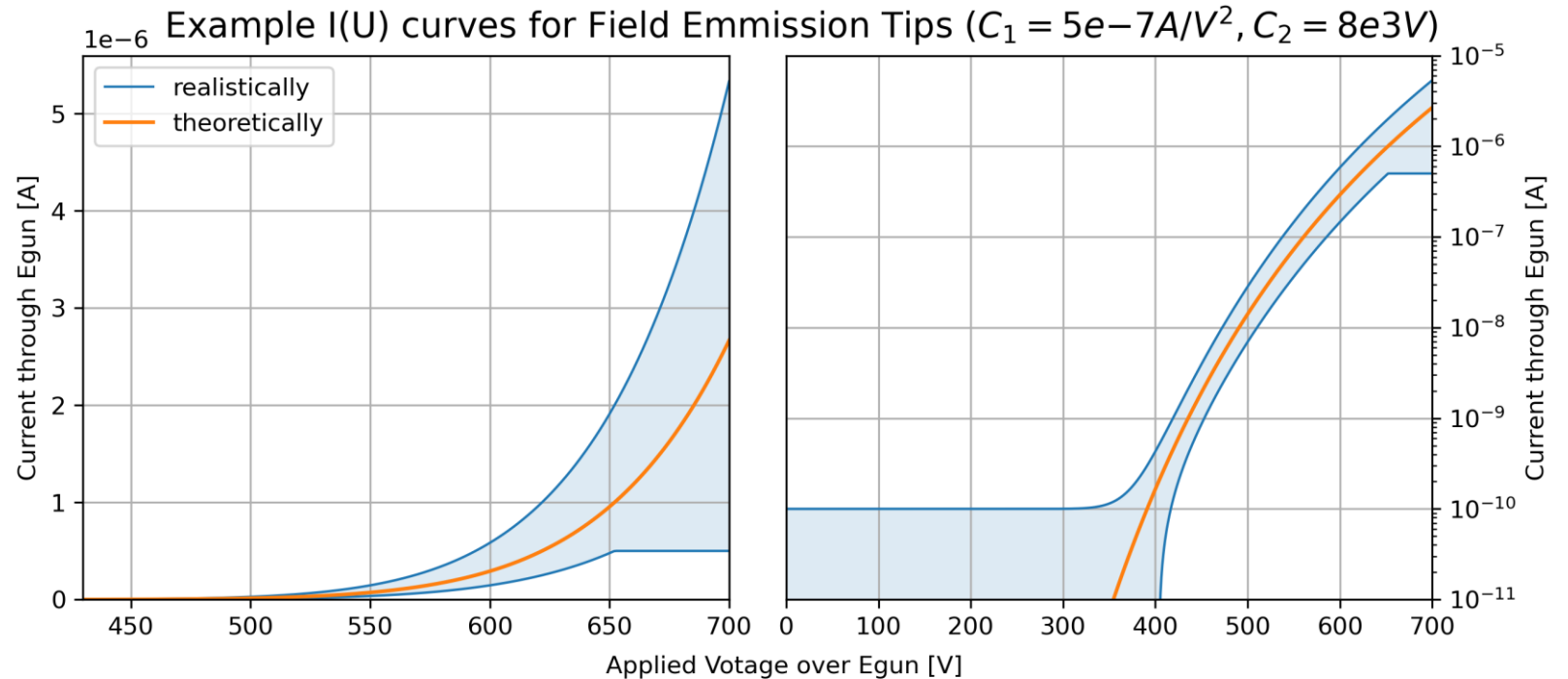
# Intro to Field Emission Tips

Potential barrier near metal surface with different applied electric fields



- Free electrons may tunnel through surface
- Stronger fields  $\rightarrow$  greater tunnelling chance

$$I(U) \propto C_1 \cdot U^2 \cdot e^{-\frac{C_2}{U}}$$





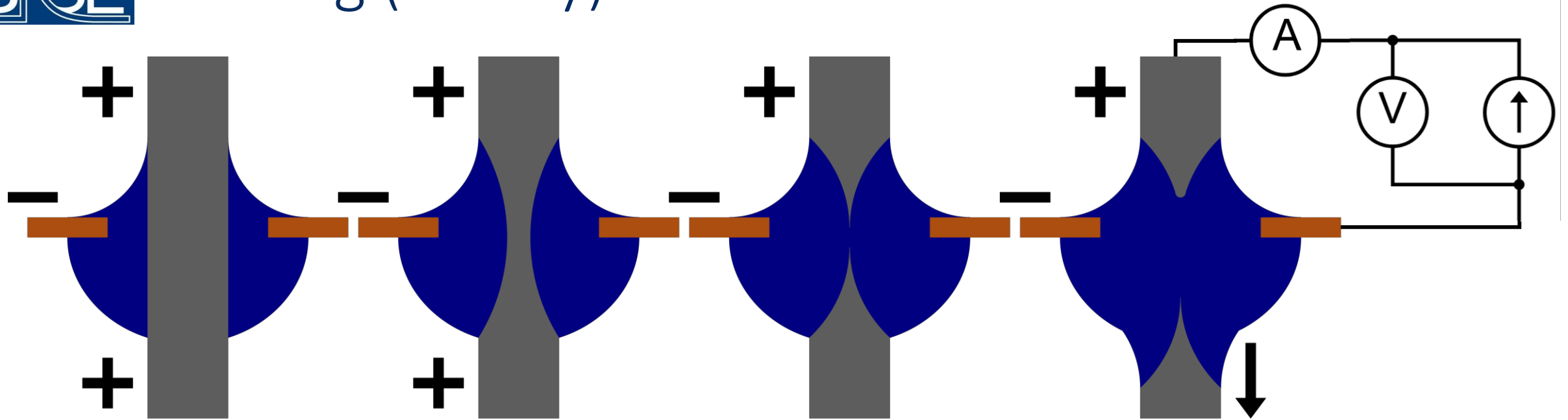
# Intro to Field Emission Tips

- We can increase voltage and decrease electrode distance to increase E-field
- Sharper tips increase E-field as well  
→ Goal: produce sharpest possible tips

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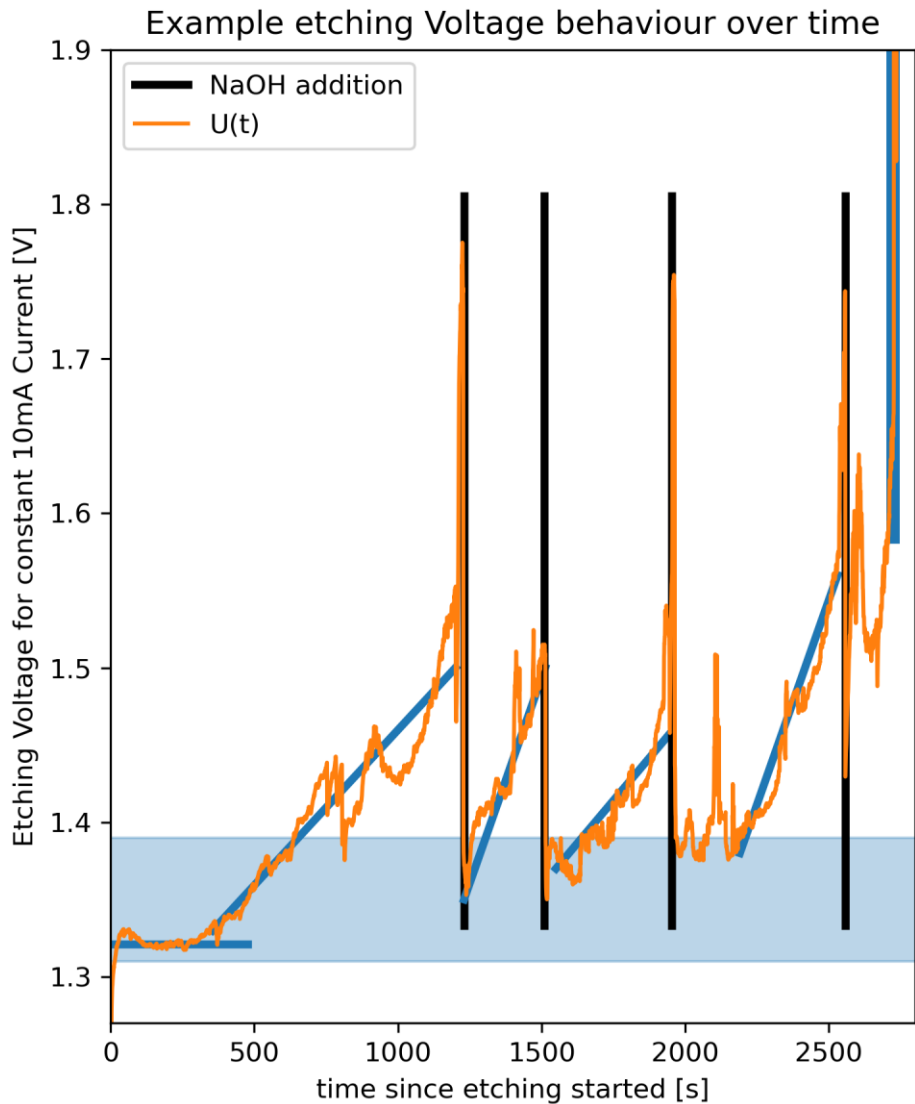
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# Etching (theory)



- Idea: inverse galvanization of tungsten wire to produce nm-sharp FE-tips
- Constant current application to etch tungsten near hole
- Separation of wire leaves lower part on floating potential  
→ etching stops, tip stays sharp

# Etching (implementation)



- NaOH used as electrolyte (3M/l, 14.5pH)
  - Three consecutive behaviours: stable, slow increase & explosion in resistance
  - NaOH is probably getting used up in electrolysis → refilling needed before explosion, otherwise the electrolysis stops
  - Also explosion in resistance after tip falls down
  - High resistance voltage oscillations

( $\text{Cu} \leftrightarrow \text{NaOH} \cdot \text{H}_2\text{O} \leftrightarrow \text{W}$  is effectively a battery with  $\approx 0.44\text{V}$  cell voltage. This makes resistance measurements without current useless)

# Etching (implementation)

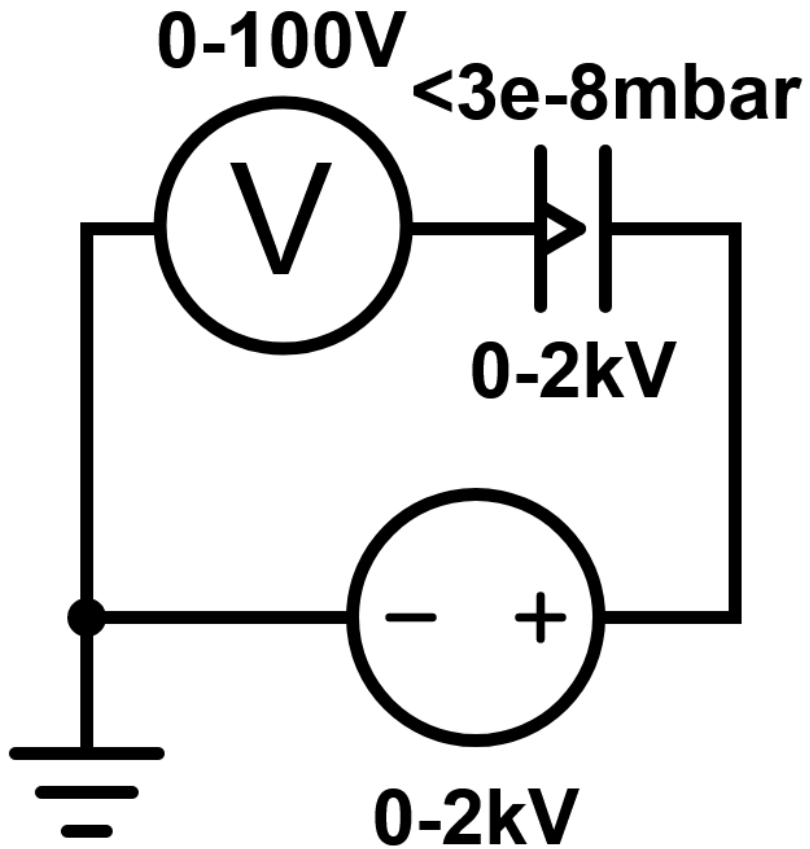


A

B

- Etching setup (see B):
  - Tungsten wire Source Measure Unit + connection
  - Guiding Rod to stabilize
  - Copper Plate with etching holes (1-6mm) and Source Measure Unit – connection
- $R_{\text{Plateau}}(I) \approx 25\Omega + \frac{1V}{I}$
- Reliably produces FE-Tips (see A), but not with reliable shapes

# Characterization (theory)



- Sweep over  $U_{\text{HV-Supply}}$ ,
- Calculate  $I_{\text{E-gun}}(U_{\text{E-gun}})$  from  $U_{\text{Voltmeter}}$

$$R_{\text{Voltmeter}} = 10\text{M}\Omega$$

$$U_{\text{HV-Supply}} = U_{\text{E-gun}} + U_{\text{Voltmeter}}$$

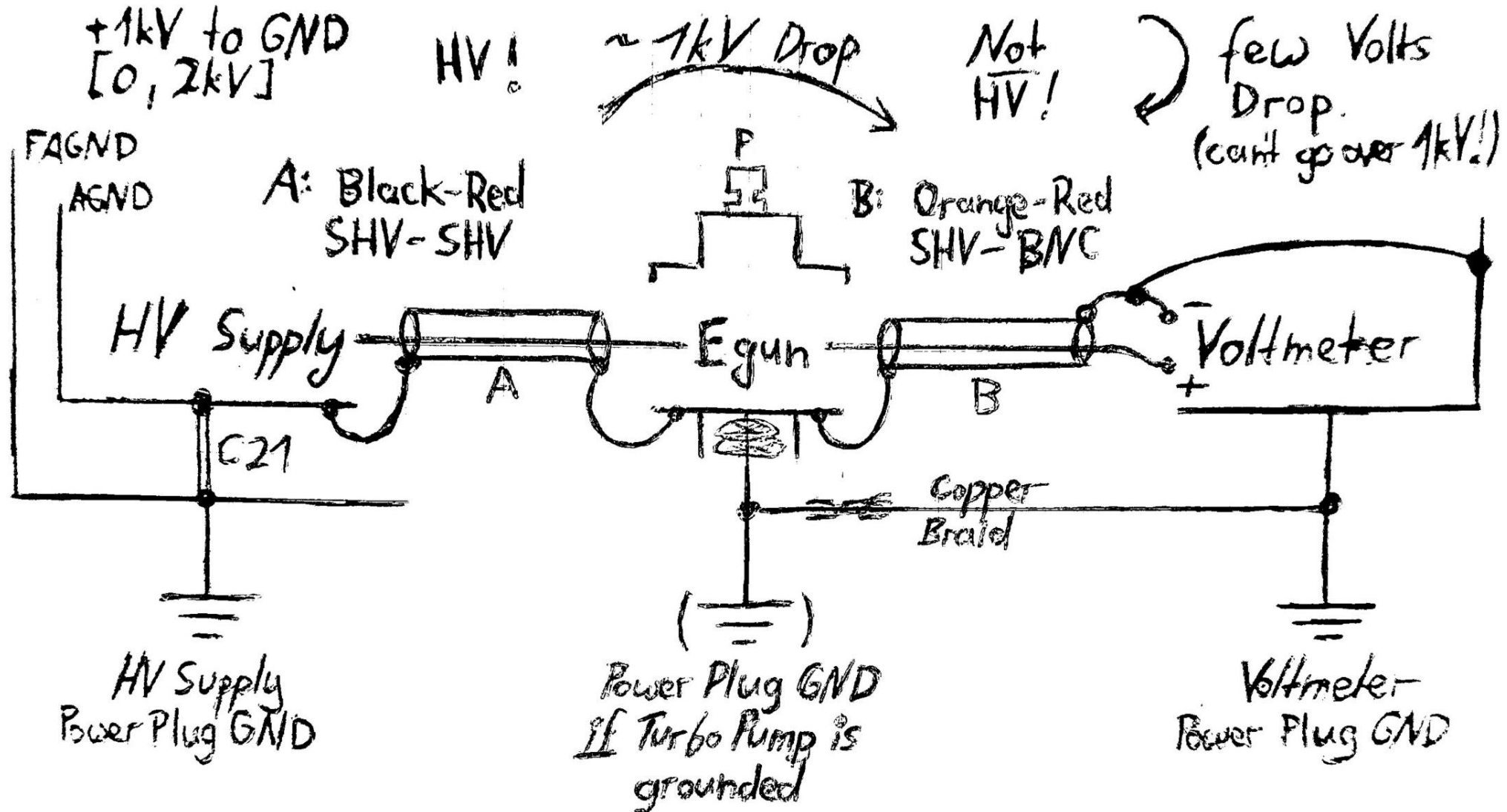
$$I_{\text{Total}} = I_{\text{E-gun}} = I_{\text{Voltmeter}}$$

$$\rightarrow U_{\text{E-gun}} = U_{\text{HV-Supply}} - U_{\text{Voltmeter}}$$

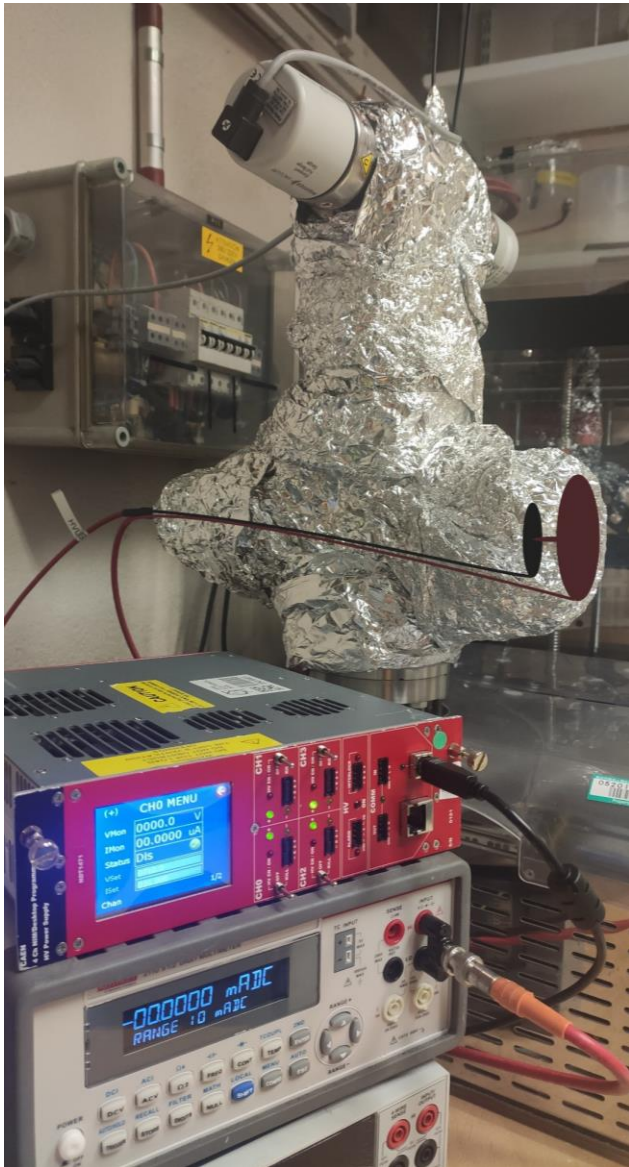
$$\rightarrow I_{\text{E-gun}} = \frac{U_{\text{Voltmeter}}}{10\text{M}\Omega}$$



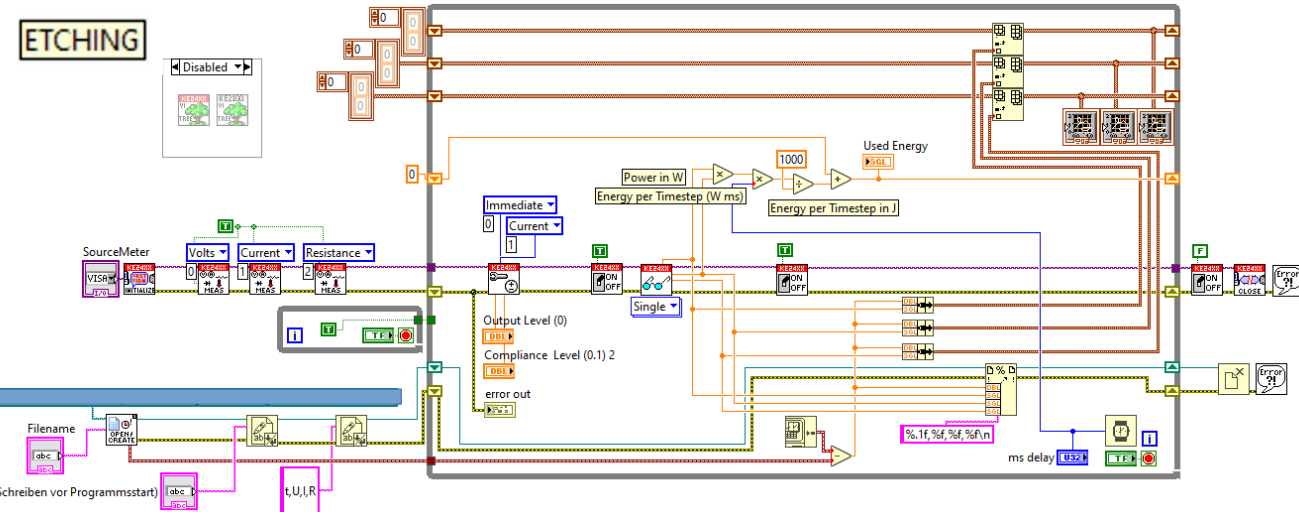
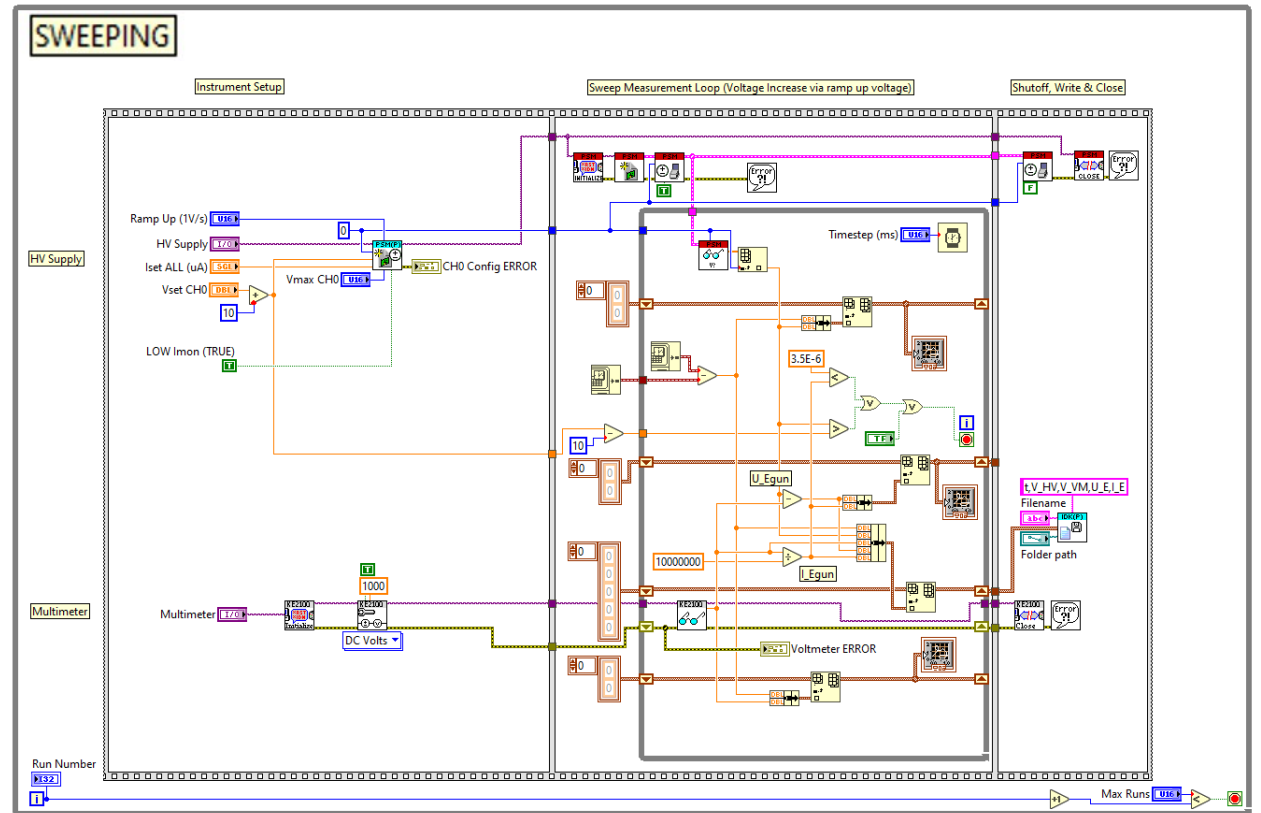
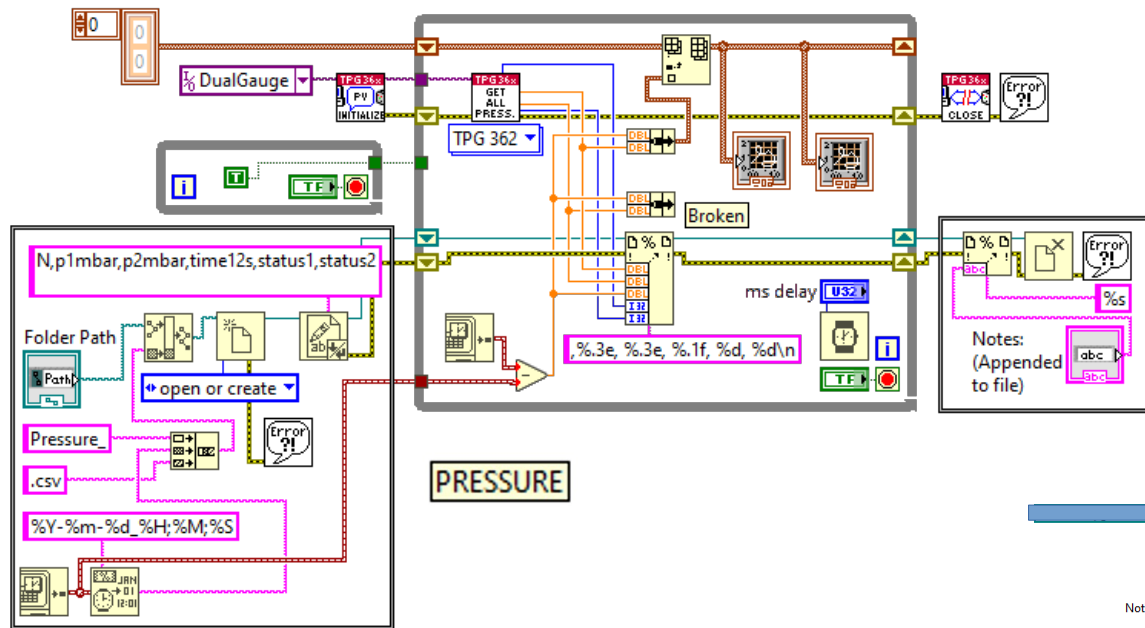
# Characterization (implementation)



# Characterization (implementation)



- Measurement and Logging VI's
  - Pressure, Etching, Characterization
- Data Analysis in Python
  - 2D, 3D, Fitting, Allen deviation

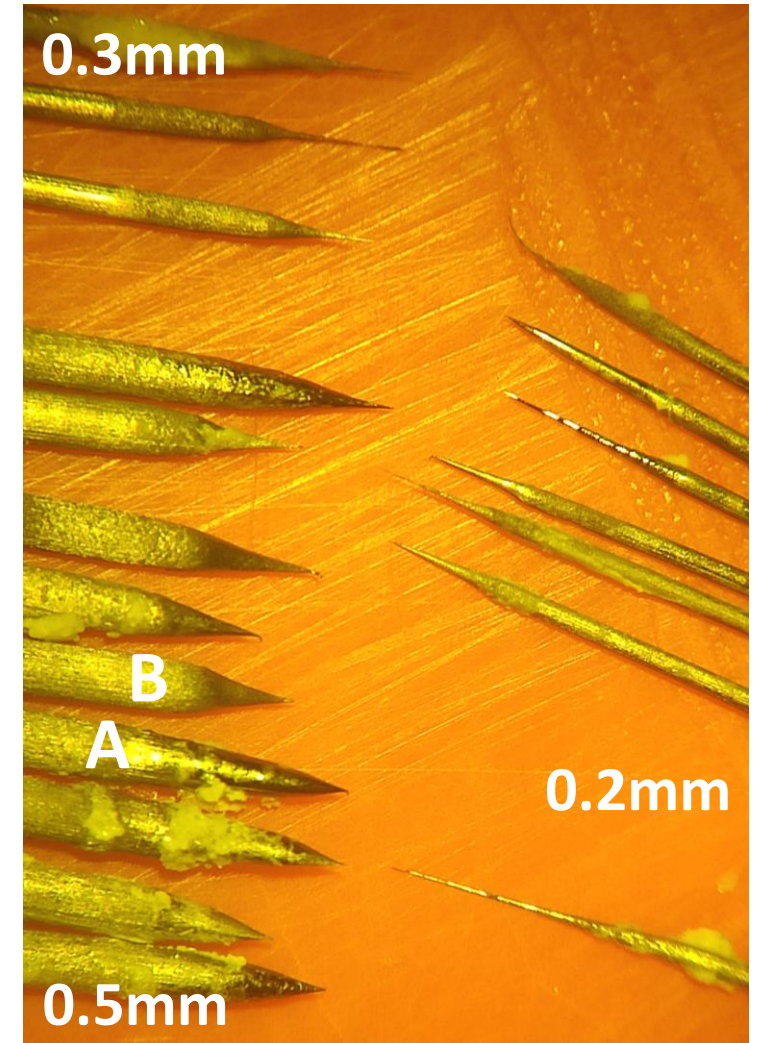


$\varnothing$ $\mu\text{m}$	500	500	500	500	300	300	500	500
V@1nA	500(50)	420(30)	450(50)	215(15)	145(15)	300(50)	450(30)	???
V@10nA	575(25)	475(25)	500(50)	235(15)	175(15)	320(50)	510(30)	???
V@100nA	700(50)	575(25)	575(25)	275(25)	195(25)	375(75)	600(50)	???
V@1 $\mu$ A	850(50)	650(50)	700(50)	325(25)	$\geq 190(?)$	$\geq 350(?)$	650(50)	???
Comment						Noisy!		(P23)

- Tested and stored Tips:

- Dependence on Parameters

- Hole size/shape:
  - may change taper length
  - bent down hole keeps drop at wire
- Concentration:
  - slower increase in resistance
  - crystallization on wire
- Current:
  - changes finish (mirrored  $\rightarrow$  matte)
  - decreases etching time
- Wire thickness:
  - leads to macroscopically duller tips
  - easier to handle and put in E-gun
  - increases etching time
- Max Voltage:
  - [not tested, kept low]
- Etching time:
  - result of other parameters

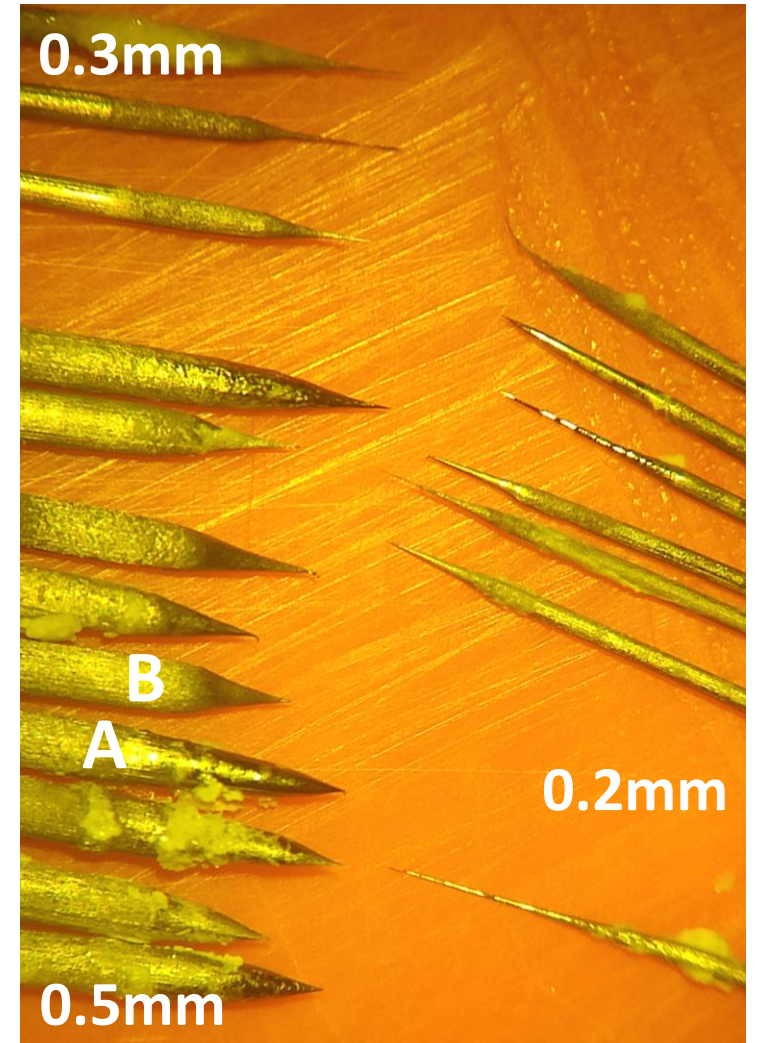


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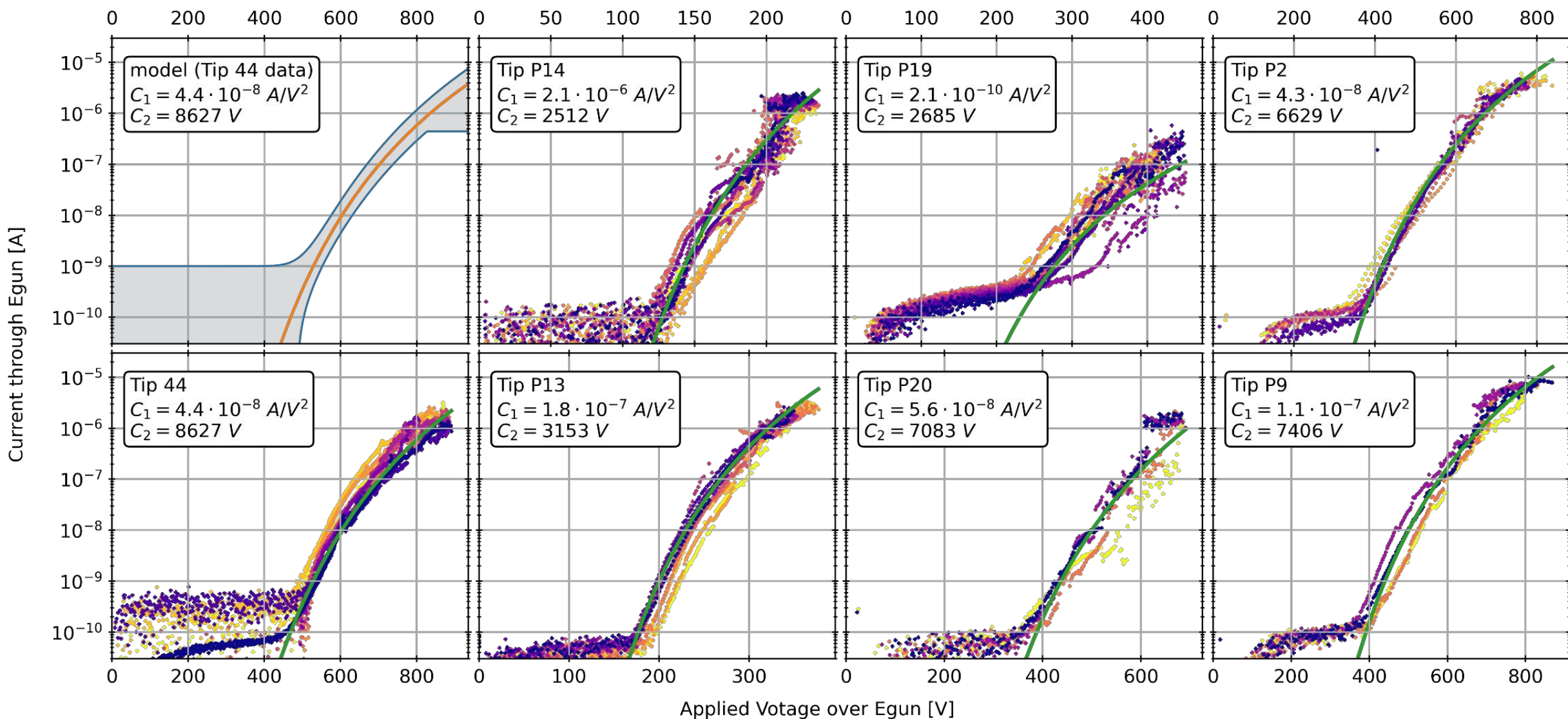
- Tested and stored Tips:

- Used and recommended Parameters

- Hole size/shape: -  $d_{\text{hole}} \in \{1.7, 1.8, 2.3, 2.8\} \text{mm}$  all good
  - 2.8mm bent down hole for production
- Concentration: - 2M R explosion after  $\approx 10^{2.2(2)} \text{s}$ 
  - 4M crystallized directly  $\rightarrow$  3M
- Current:
  - $I \in \{5, 10, 50, 100\} \text{mA}$
  - 5mA|<sub>0.2mm</sub>, 10mA|<sub>0.3mm, 0.5mm</sub>
- Wire thickness: -  $d_{\text{wire}} \in \{0.2, 0.3, 0.5\} \text{mm}$ 
  - mainly made 0.5mm tips
  - 0.3mm bent in E-gun, but usable
- Max Voltage: -  $V_{\text{max}} < 20V$  (5V, 3V, ...)
- Etching time: -  $t(d_{\text{wire}}, I) \approx 700 \left(\frac{d_{\text{wire}}}{\text{mm}}\right)^2 \left(\frac{I}{\text{mA}}\right)^{-0.8}$   
(very roughly, phenomenologically)



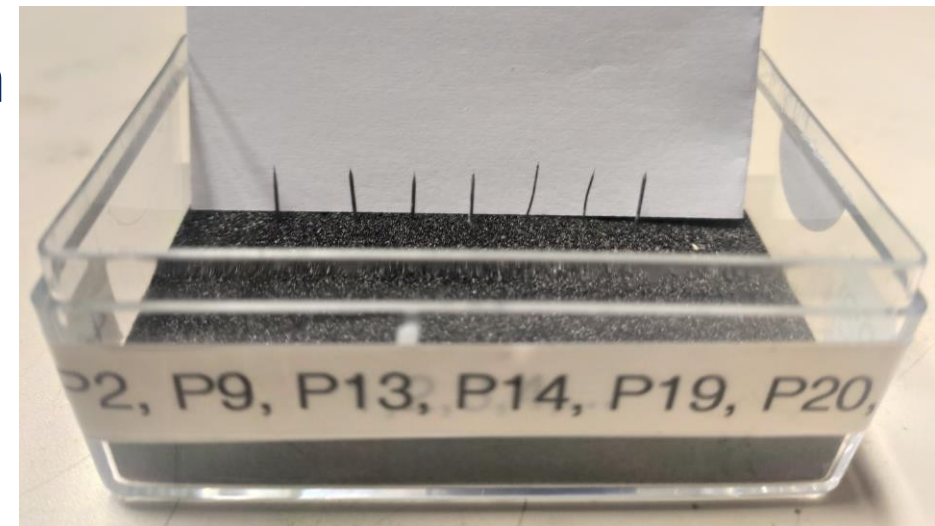
## Behaviour of categorized Field Emission Tips



# Conclusions & further work

- Tips now stored in closed box, stuck in foam with tip side up
- Code (python, LabVIEW), presentation and important logs in  
“G: \ [INTERNAL PATH]”
- Explicitly characterize tip parameter dependencies
  - currently only done to the extend needed
- Solve NaOH depletion / crystallization problem

Thanks for the Internship ^^



# Production of new E-gun tips

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